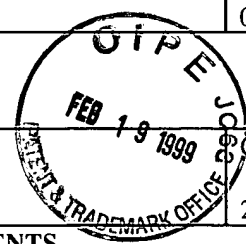


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	ATM-337	09/200,495
	APPLICANT	
	Van Buskirk et al	
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U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
SA		5,783,716	7/21/98	Baum et al	556	136	
SK		5,719,417	2/17/98	Roeder et al	257	295	
		08/960,915		Hintermaier			11/20/97
SL		5,859,274	1/12/99	Baum et al	556	76	

FOREIGN PATENT DOCUMENTS								
		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO	

OTHER DOCUMENTS (Including Author, Title, Journal-Date, Page Number, Etc.)		
SA		Rosnagel, S.M. et al, "Thin high atomic weight refractor film deposition for diffusion barrier, adhesion layer, and seed Layer applications", <i>J. Vac. Sci. Technol. B</i> , Vol. 14, No. 3, May/Jun 1996 pp. 1820-82
SL		J.L.Vossen, W. Kern, Eds., <i>Thin Film Processes II</i> , Academic Press, Boston, MA, 1991, pp. 763

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EXAMINER	DATE CONSIDERED
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.